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ABSTRACT OF THE DISCLOSURE

Electrically Floating Shield in a Plasma Reactor

by

Peijun Ding
Zheng Xu
Jianming Fu

In a plasma reactor, especially one intended for physical vapor deposition (PVD) onto semiconductor substrates, a shield disposed in front of the chamber walls between the PVD target and the substrates to protect the chamber walls. According to the invention, the shield is left electrically floating so that electrically charged ions and electrons emanating from the plasma or target and impinging upon the shield charge it to the point that the electrical flux is repelled.

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